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摘要：原子力显微镜（Atomic Force Microscopy）已成为在纳米尺度对样品进行观察和操纵的重要工具。基于原子力显微镜观测的重定位技术提供一种微观区域内对样品处理前后原位对比观测的方法。本文利用坐标实时显示的程控高精度样品台系统，联合使用表面双标记定位法，建立一种新的重定位方法，方便、高效地实现样品重定位AFM成像。

关键词：原子力显微镜, 重定位成像, 表面标记, 程控高精度样品台系统

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[Reposition imaging technique of AFM with program controlled sample stage](#)

Abstract: Atomic force microscopy (AFM) has been an important tool for observing and manipulating samples at nanometer scale. Reposition imaging technique of AFM provides a method to compare the differences between the former sample and the disposed sample at the same position. In this paper, an new accurate and efficient reposition imaging technique of AFM for multi area has been developed by employing the AFM equipped with program controlled high resolution sample stage system and using two surface marks in the sample.

Key words: Atomic force microscope, Reposition imaging, Surface mark, Program controlled high resolution sample stage

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